

an illumination optical system which irradiates an exposure illumination light beam;

wherein the mask stage is also positionable parallel to the X-direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device;

wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the Y-direction and X-direction and can be rotated about the axis of rotation of the mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the Y-direction; and

wherein a magnet system and an electric coil system belong to the first linear motor, while the second linear motor comprises a stationary part and a movable part which is displaceable parallel to the Y-direction over a guide of the stationary part, the magnet system of the first linear motor being fastened to the mask stage and the electric coil system of the first linear motor being fastened to the movable part of the second linear motor.

31. (Amended) A lithographic device comprising the following elements which are supported in that order:

a substrate stage which can be positioned by a first positioning device parallel to a first direction which is perpendicular to a vertical Z-direction and a second direction which is perpendicular to the first direction and to the Z-direction;

an imaging system with a main axis directed parallel to the Z-direction;

a mask stage which can be positioned parallel to the first direction by a second positioning device; and

an illumination optical system which irradiates an exposure illumination light beam;

wherein the mask stage is also positionable parallel to the second direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device;

wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the first direction and the second direction and can be rotated about the axis of rotation of the mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the first direction; and

wherein a magnet system and an electric coil system belong to the first linear motor, while the second linear motor comprises a stationary part and a movable part which is displaceable parallel to the first direction over a guide of the stationary part, the magnet system of the first linear motor being fastened to the mask stage and the electric coil system of the first linear motor being fastened to the movable part of the second linear motor.

Please add the following claims 32 and 33:

--32. (New) A lithographic device comprising the following elements which are arranged in that order:

a substrate stage which can be positioned by a first positioning device parallel to a first direction which is perpendicular to a vertical Z-direction and a second direction which is perpendicular to the first direction and to the Z-direction;

an imaging system with a main axis directed parallel to the Z-direction;

a mask stage which can be positioned parallel to the first direction by a second positioning device; and

an illumination optical system which irradiates an exposure illumination light beam;

wherein the mask stage is also positionable parallel to the second direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device; and

wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the first direction and the second direction and can be rotated about the axis of rotation of the mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the first direction.--

--33. (New) A lithographic device comprising the following elements which are arranged in that order:

a substrate stage which can be positioned by a first positioning device parallel to a first direction which is perpendicular to a vertical Z-direction and a second direction which is perpendicular to the first direction and to the Z-direction;

an imaging system with a main axis directed parallel to the Z-direction;

a mask stage which can be positioned parallel to the first direction by a second positioning device; and

an illumination optical system which irradiates an exposure illumination light beam;

wherein the mask stage is also positionable parallel to the second direction and rotatable about an axis of rotation which is parallel to the Z-direction by the second positioning device;

wherein the second positioning device is provided with a first linear motor by means of which the mask stage can be positioned over comparatively small movement parallel to the first direction and the second direction and can be rotated about the axis of rotation of the mask stage and a second linear motor by means of which the mask stage can be positioned over comparatively great movement parallel to the first direction; and